

Full length article

First-principles study of two-dimensional $\text{MoN}_2\text{X}_2\text{Y}_2$ ($\text{X}=\text{B}\sim\text{In}$, $\text{Y}=\text{N}\sim\text{Te}$) nanosheets: The III–VI analogues of MoSi_2N_4 with peculiar electronic and magnetic properties

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ABSTRACT

The recent discovery of MoSi_2N_4 nanosheet boosts researches on the layered MA_2Z_4 materials. Utilizing first-principles calculations, we investigate the isoelectronic and isostructural analogues of MoSi_2N_4 , i.e. group III–VI $\text{MoN}_2\text{X}_2\text{Y}_2$ ($\text{X}=\text{B}\sim\text{In}$, $\text{Y}=\text{N}\sim\text{Te}$) nanosheets. Nine III–VI XY combinations are revealed to form stable $\text{MoN}_2\text{X}_2\text{Y}_2$ systems with robust dynamical, thermal and energetic stability. They can be indirect-gap semiconductors or metals depending on the XY compositions. There is a linear relationship between the gap size and lattice constant of semiconducting $\text{MoN}_2\text{X}_2\text{Y}_2$ systems. More interestingly, a Mexican-hat-like band dispersion appears in the top valence band of $\text{MoN}_2\text{X}_2\text{Y}_2$ ($\text{XY}=\text{AlO}$, GaO , InO) nanosheets, for which the hole doping can induce Stoner ferromagnetism and convert the systems into half-metals. For the van der Waals heterostructures formed by $\text{MoN}_2\text{X}_2\text{Y}_2$ ($\text{XY}=\text{BS}$, AlO) and MoSi_2N_4 nanosheets, they exhibit versatile and strain-tunable band alignments, including the straddling-gap type-I, staggered-gap type-II, and broken-gap type-III ones. Our study demonstrates that the composition of surface layers is a new degree to manipulate the electronic structure of MA_2Z_4 -based materials and it will bring tunable electronic and magnetic behaviours for the electronics, spintronics, and nano-device applications.

1. Introduction

Layered transition-metal (TM) systems, including dichalcogenides (TMDs [1,2]), dinitrides (TMDNs [3,4]), diborides (TMDBs [5,6]), dihydrides (TMDHs [7,8]), as well as carbides and nitrides (MXenes [9,10]), are a plethora of two-dimensional (2D) materials with promising electronic and magnetic properties. Very recently, a new member of layered materials, i.e. 2D MoSi_2N_4 system, has been synthesized in the chemical vapour deposition experiment [11]. This discovery boosts researches on the layered MA_2Z_4 materials, where M belongs to the 4d/5d TM elements, A is the Si or Ge element, and Z stands for N, P, As ones [12]. The MoSi_2N_4 nanosheet possesses a semiconducting property like the MoS_2 system [13,14], which also exhibits the spin-valley coupling electronic and optical behaviours [15–17]. Particular physical properties, including large piezoelectricity [18,19], high lattice thermal conductivity [20,21], high-efficient electrocatalytic activity [22–24], and good molecular detection capability [25,26], are reported in this MoSi_2N_4 system, which are even superior to the MoS_2 one. Due to the protection of outlying SiN surface, the MoSi_2N_4 nanosheet can exhibit a tunable Schottky barrier at the metal/semiconductor contact [27], which would be a good air-stable channel material for the

sub-5-nm MOSFETs [28]. Novel bilayer heterostructures can be created by coupling the MoSi_2N_4 nanosheet with other 2D systems, and the formed heterostructures present versatile electronic properties that can be further tuned by external strain and electric-field [29–32].

Analogous to the TMDs, the effects of TM elements on the electronic structures of MA_2Z_4 nanosheets have been highlighted by scientists [33,34]. For the MSi_2N_4 systems, they can be metallic or semiconducting depending on the valence electron counts (VECs) rather than the structural phases [35,36]. With even VECs, the group-IV/-VI MA_2Z_4 nanosheets are semiconductors, among which the HfSi_2N_4 one is identified as a promising candidate for photocatalytic CO_2 reduction [37–39]. On the other hand, the group-V MA_2Z_4 systems with odds VECs are metals, which are predicted as appealing electrocatalysts for the oxygen reduction and hydrogen evolution reactions [40–42]. The VSi_2N_4 system is even reported as a rare valley-half-semiconductor [43,44]. It would be noted that the MSi_2N_4 nanosheet can be regarded as a MN_2 nanosheet sandwiched between two SiN surfaces [45]. Thus, comparing to the TMDs, there will be a new degree, i.e. the composition of surface layer, that can manipulate the electronic structures of MSi_2N_4

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nanosheets. Following the design idea of atomic transmutation [46], the SiN surfaces would be replaced by the isoelectronic III–VI ones to form the $\text{MN}_2\text{X}_2\text{Y}_2$ nanosheet, which has the same VECs to the MSi_2N_4 one [47].

In the experiment, the MoSi_2N_4 nanosheet has been synthesized by the chemical vapour deposition (CVD) growth of molybdenum nitride with additional silicon substance [11]. Thus, it could be expected that the $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets would be obtained by similar CVD method with appropriate III–VI additives. Besides that, in the literature, the analogous septuple-atomic-layer MX_2Y_4 materials, including MnAl_2S_4 , MnGa_2S_4 , FeIn_2S_4 , FeIn_2Se_4 , and $\text{FeIn}_2\text{S}_2\text{Se}_2$, have already been experimentally reported [48–50]. Thus, through the substitution reactions, the $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets may also be produced from these layered MX_2Y_4 materials. However, two isostructural and isoelectronic systems may exhibit distinct electronic behaviours as in the case of graphene and BN nanosheets [51]. Thus, it can be expected that the $\text{MN}_2\text{X}_2\text{Y}_2$ systems will also possess peculiar electronic and magnetic properties. However, even for the MoSi_2N_4 one, the corresponding group III–VI derivatives have not been studied yet. How about the structural stability of these $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets with different XY compositions? What kind of fascinating electronic properties will appear in these systems? When the $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets are coupled with MoSi_2N_4 one, how will the heterostructures behave like? To address these issues, we perform a computational study to systematically investigate the structural stability, electronic and magnetic properties of $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets.

2. Computational details

The first-principles calculations are performed by the VASP code [52], which utilizes Perdew–Burke–Ernzerhof (PBE) projector-augmented wave pseudo-potentials and plane-wave basis sets with a cut-off energy of 500 eV. The Brillouin zone is sampled by a Wiseman–McGill–Mueller k -grid with minimum period distances of 40 and 50 Å in the relaxation and static calculations, respectively [53]. The Grimme-D3 correction with Becke–Jonson damping is adopted for the van der Waals interaction in the bilayer systems [54]. A vacuum layer of about 15 Å is used to simulate the isolated 2D systems, and all the geometrical structures are fully relaxed until the maximum residual force is less than 0.01 eV/Å. The obtained electronic structures are also checked by the Heyd–Scuseria–Ernzerhof (HSE) functional, for which an interpolation of Wannier function is used to obtain the hybrid band structure [55]. The phonon spectra are calculated by the Phonopy code on a 5×5 supercell via the finite-displacement method [56], where a rotational sum rule is enforced on the force constants by the Hiphive package [57]. Ab initio molecular dynamic (AIMD) simulations are performed on a 4×4 supercell, which adopt the canonical NVT ensemble with a Nose thermostat of 300 K. The step time is set to 1 fs and the total simulated time is 5 ps, i.e. up to 5000 steps.

3. Results and discussion

Figs. 1(a) and (b) depict the geometrical structures of $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets, which are derived from MoSi_2N_4 via the replacement of SiN surfaces by the isoelectronic III–VI XY ones. Here, all the possible combinations from group III and VI elements in the period 2–5 are considered, and there are sixteen $\text{MoN}_2\text{X}_2\text{Y}_2$ candidates. The corresponding geometrical and energetic information of these $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets is provided in Figs. 1(c) and (d). Compared to the pristine MoSi_2N_4 system ($a=2.908$ Å, $h=7.002$ Å), most $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets have longer lattice constants and bigger layer thickness. Through the phonon calculations, three $\text{MoN}_2\text{X}_2\text{Y}_2$ (XY=GaTe, InSe, InTe) nanosheets are filtered out due to the remarkable imaginary frequencies in their Brillouin zone. While all the other ones are dynamically stable as shown in Fig. S1 of supplementary material. Since in the literature, the MA_2Z_4 materials can be viewed as the 2H-phase MZ_2 nanosheet inserted between the

InSe-type A_2Z_2 layers [33], the formation energy (E_{form}) of $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets is calculated as $E_{form} = E_{\text{MoN}_2\text{X}_2\text{Y}_2} - E_{\text{MoN}_2} - E_{\text{X}_2\text{Y}_2}$, where $E_{\text{MoN}_2\text{X}_2\text{Y}_2}$ is the total energy of $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheet, E_{MoN_2} is the energy of the isolated MoN_2 nanosheet at the ferromagnetic state, and $E_{\text{X}_2\text{Y}_2}$ is the energy of the InSe-like III–VI X_2Y_2 nanosheet. According to this definition, a negative (positive) E_{form} corresponds to an exothermic (endothermic) synthesis process for the corresponding $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheet, which is energetically favourable (unfavourable) comparing to the isolated MoN_2 and X_2Y_2 layers. The obtained formation energies of $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets are displayed in Fig. 1(d). It can be seen that among the thirteen dynamically stable systems, three $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets (XY=AlTe, GaSe, InS) are energetically unfavourable due to their positive E_{form} values. For the remaining ten $\text{MoN}_2\text{X}_2\text{Y}_2$ systems, the AIMD simulations are further conducted to check their thermal stability. As indicated in Fig. S2 of supplementary material, except the $\text{MoN}_2\text{B}_2\text{O}_2$, all the other nine $\text{MoN}_2\text{X}_2\text{Y}_2$ systems are thermally stable at room temperature. The structural integrity is well kept during the AIMD simulations and the total energies are just fluctuated around the equilibrium values. After the AIMD simulations, there is no bond breaking and only small distortions appear in the final configuration, which can be recovered by the structural relaxation. Here, combined with the phonon, AIMD and formation energy results, good structural stability is confirmed in the nine $\text{MoN}_2\text{X}_2\text{Y}_2$ (XY=BS, BSe, BTe, AlO, AlS, AlSe, GaO, GaS, and InO) nanosheets, which can withstand the free-standing form at room temperature. This suggests those $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets will be experimentally accessible like the MoSi_2N_4 system.

Regarding to the unstable $\text{MoN}_2\text{X}_2\text{Y}_2$ systems, the crystal orbital Hamilton population (COHP) bonding analysis are performed to get more insights into their instability. The integral value of –COHP up to the Fermi level (–ICOHP) are provided in the Tab. S1 of supplementary material. Here, the big (small) –ICOHP value corresponds to a strong (weak) bond [58,59]. It can be seen that for the dynamically unstable $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets (XY=GaTe, InSe, InTe), their X–Y bonds are much weaker than the stable ones, which leads to the dynamical instability. While for the energetically unstable ones (XY=AlTe, GaSe, InS), the Mo–N, and N–X, and X–Y bonds are also weaker, which makes the system energetically unfavourable. For the thermally unstable $\text{MoN}_2\text{B}_2\text{O}_2$ nanosheet, although the –ICOHP value of B–O bond seems to be big, the corresponding bond length is as long as 1.64 Å, which is much larger than the common B–O bonds (1.28–1.43 Å) in the boron–oxygen materials [60]. This indicates that the B–O bonds are stretched significantly to accommodate the MoN_2 layer, which become largely weakened in the $\text{MoN}_2\text{B}_2\text{O}_2$ nanosheet. As a result, the regular BO hexagons will be broken during the 300 K AIMD simulation, and the surface layer is transformed to an amorphous morphology as shown in Fig. S3 of supplementary material. Thus, strong enough X–Y bonds with matched bond lengths to the MoN_2 layer are the prerequisite for the stability of $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets.

Now, we pay main attention to the electronic structures of stable $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets. The pristine MoSi_2N_4 nanosheet is an indirect-gap semiconductor, whose valence band maximum (VBM) is located at the Γ point and the conduction band minimum (CBM) lies at the K point [13]. Similar band features exist in the semiconducting $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets as shown in Fig. 2, which are also indirect-gap semiconductors with the VBM and CBM at the Γ and K points, respectively. Through the analysis of orbital-resolved fat bands, it is found that the bands around the Fermi level are primarily originated from the Mo atoms. The Mo d_{z^2} orbital dominates the top valence band around the Γ and the bottom conduction band around the K point, while the Mo d_{xy/x^2-y^2} orbitals make an important contribution to the top valence band around the K point. These band compositions resemble the MoSi_2N_4 and MoS_2 cases [13]. Such fat band result is also consistent with the partial charge densities of band edges in Fig. 2(d). It can be seen that the VBM is composed of the Mo d_{z^2} and N p_z orbitals and the CBM is made up of the Mo d_{z^2} orbital solely. For the $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets, a linear relationship is present between

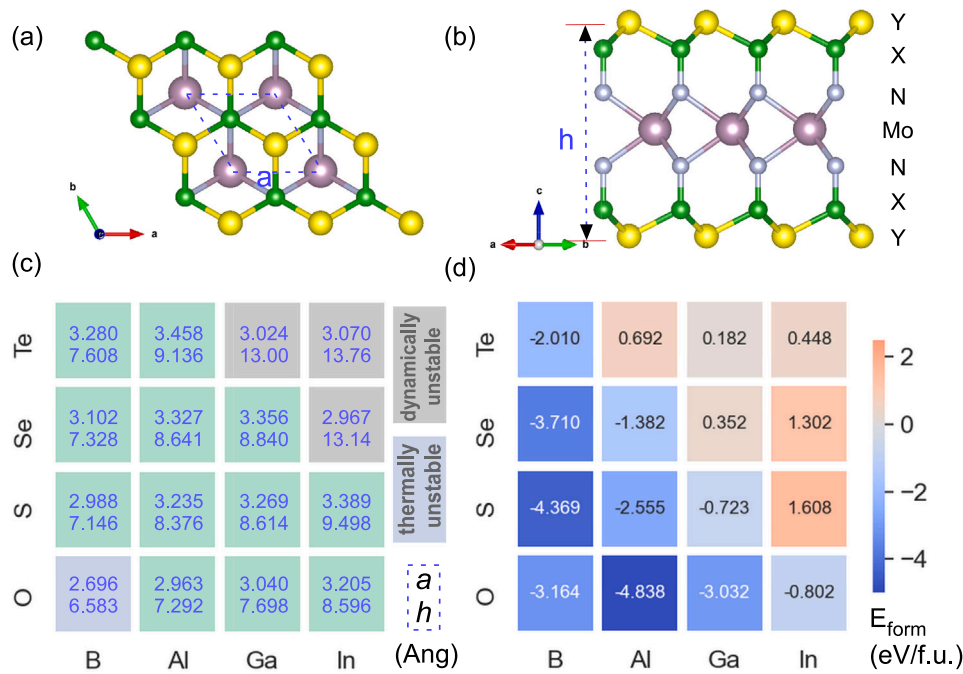


Fig. 1. (a) The top and (b) lateral view of $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheet. (c) The geometrical structures (lattice constant a and thickness h) and (d) energetic properties (formation energies E_{form}) of $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets. The dynamically and thermally unstable systems are marked in (c).

the gap size and lattice constant as shown in Fig. 2(b). A long a value leads to a smaller band gap. This result is reasonable because the coupling between the Mo d_{z^2} and N p_z orbitals will be weakened in the case of a long lattice constant. As a result, the VBM and CBM, which are both dominated by the Mo d_{z^2} orbital, will approach each other and result in a reduced band gap. Such phenomenon has also been reported in the stretched MoSi_2N_4 nanosheet [61,62]. Here, due to the longer lattice constants, all the semiconducting $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets have smaller band gaps than the MoSi_2N_4 one in Fig. 2(b). It will be noted that the linear relation will be deviated if the $\text{MoN}_2\text{X}_2\text{Y}_2$ systems become metallic. When the lattice constant exceeds 3.2 Å, the gap is closed in the $\text{MoN}_2\text{X}_2\text{Y}_2$ (XY=AlS, GaS, AlSe, BTe) nanosheets, which present a metallic behaviour by the PBE calculation. The HSE calculation predicts similar metallic feature in these systems except for the $\text{MoN}_2\text{Al}_2\text{S}_2$ nanosheet, which is still semiconducting with a small band gap of 0.023 eV from the HSE result. In view of the strong dependence of band gap on the lattice constant, it can be expected that the strain engineering can effectively tune the metallic behaviour of these $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets. As indicated in Fig. 2(f), the overlap between the bottom conduction band at the K point and the top valence band at Γ point is decreased (increased) under the compressive (tensile) strains. For the $\text{MoN}_2\text{Al}_2\text{S}_2$ and $\text{MoN}_2\text{Ga}_2\text{S}_2$ nanosheets, the overlap can be diminished by small strains of about -0.02 . Thus a metal-semiconductor transition can be easily triggered in these $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets by small strains. Such critical strains are much smaller than the one required for the metal-semiconductor transition in the MoSi_2N_4 system (more than 10% for the bilayer case [63]), which are experimental affordable and endow those $\text{MoN}_2\text{X}_2\text{Y}_2$ systems promising nanomechanical sensor applications.

It would be noted that for the $\text{MoN}_2\text{X}_2\text{Y}_2$ (XY=AlO, GaO, InO) systems, their top valence bands are dispersionless around the Γ point. Taking the $\text{MoN}_2\text{Al}_2\text{O}_2$ nanosheet as an example in Fig. 3(a), a Mexican-hat-like band dispersion can be clearly visualized in the top valence band. A high peak is present in the density of states (DOSs), which causes a van Hove singularity in the valence band edge. Consequently, when the Fermi level is shifted into the DOSs peak through the hole doping, remarkable electron-electron repulsion will be present for the electrons at the Fermi surface. According to the Stoner theory [64],

these electrons will prefer to be spin-polarized, which reduces the DOS at the Fermi level and further lowers the total energy. Thus, a spin-polarized calculation is performed to check the possible Stoner magnetism in the hole-doped $\text{MoN}_2\text{Al}_2\text{O}_2$ nanosheet. As shown in Fig. 3(b), the doped holes are fully spin-polarized when the hole concentration (q_h) is in the range of about $[0.5, 6] \times 10^{13} \text{ cm}^{-2}$. The corresponding energy gain from the spin-polarization (ΔE_s) is up to 2.8 meV/hole in this $\text{MoN}_2\text{Al}_2\text{O}_2$ nanosheet at $q_h = 4 \times 10^{13} \text{ cm}^{-2}$, which is comparable to the data of hole-doped GaS, GaSe, and InSe systems (2–3 meV/hole) [64,65] and is bigger than the GaTe and InTe ones (1 meV/hole) [65]. It would be noted that in the HSE calculation, the top valence band becomes flat around the Γ point as shown in Fig. 3(a). The valence band edge at the Γ point is merely 0.001 eV lower than the VBM, which makes the Mexican-hat-like dispersion feature less obvious than the PBE one. Such discrepancy between the PBE and HSE results will be attributed to the different rates of band components (see Fig. S4 of supplementary material). However, the flat band from the HSE calculation also produces a high DOS peak in the valence band edge, which facilitates hole-induced magnetism like the PBE case.

Accompanied with the magnetism, an intriguing half-metallic behaviour is present in the hole-doped $\text{MoN}_2\text{Al}_2\text{O}_2$ nanosheet. As shown in Fig. 3(c), there is a noticeable exchange splitting in the top valence band, which is 0.027/0.157 eV at the Γ point from the PBE/HSE result. Owing to the hole doping, the Fermi level only crosses the spin down valence band and causes a half-metallic behaviour. The half-metallic gap, which is the energy of topmost occupied band relative to the Fermi level, is 0.011/0.097 eV by the PBE/HSE calculation. In addition to the ferromagnetic coupling, the antiferromagnetic coupling is also examined for the doped $\text{MoN}_2\text{Al}_2\text{O}_2$ nanosheet. However, it always converges to the ferromagnetic coupling in the static calculation, confirming that the hole-doped $\text{MoN}_2\text{Al}_2\text{O}_2$ system possesses a stable ferromagnetic state. For the doped systems, the Curie temperature (T_c) is estimated by a mean-field theory approach [64,65]. The temperature effect is taken into account as a smearing factor in the Fermi-Dirac distribution function. Through minimizing the free energy of electrons at finite temperature, the T_c value can be evaluated from the dependence of magnetic moment on the temperature. As indicated in Fig. 3(d), the estimated T_c is 85 K in the hole-doped $\text{MoN}_2\text{Al}_2\text{O}_2$ nanosheet, which

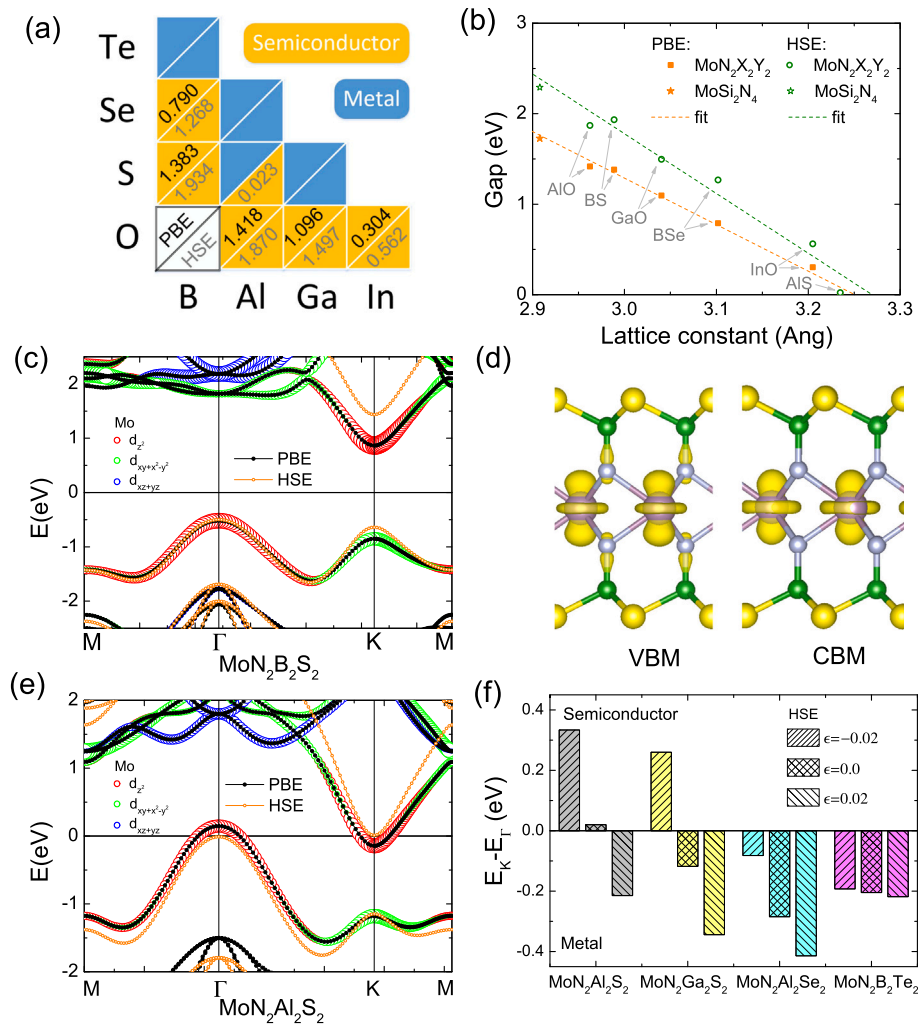


Fig. 2. (a) The electronic behaviours of stable $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets, where the PBE/HSE gaps are also labelled out for the semiconductors. (b) The variation of gap size versus lattice constant in the $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets. The orbital-resolved fat bands of (c) $\text{MoN}_2\text{B}_2\text{S}_2$ and (e) $\text{MoN}_2\text{Al}_2\text{S}_2$ nanosheets. (d) The partial charge densities of the VBM and CBM in the $\text{MoN}_2\text{B}_2\text{S}_2$ nanosheet. (f) The strain-induced gap variation of metallic $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets. Here, E_K/E_T is the energy of bottom conduction/top valence band at the K/Γ point, and the positive (negative) energy difference between them means a semiconducting (metallic) feature in the corresponding $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheet.

is similar to the GaSe counterpart (91 K [64]). For the hole-doped $\text{MoN}_2\text{Ga}_2\text{O}_2$ and $\text{MoN}_2\text{In}_2\text{O}_2$ nanosheets, their maximum ΔE_s are 1.6 and 0.8 meV/hole and the corresponding T_c are 71 and 65 K as shown in Figs. 3(b) and (d), respectively. Thus, a low-temperature condition is required to realize the hole-doped ferromagnetism and half-metallicity in these $\text{MoN}_2\text{X}_2\text{Y}_2$ ($\text{XY} = \text{AlO}, \text{GaO}, \text{InO}$) nanosheets. Fortunately, the compressive strain, which makes the top valence band flatter, can help to increase T_c . For the $\text{MoN}_2\text{Al}_2\text{O}_2$ nanosheet, as indicated in Fig. 3(d), the T_c will be raised to 92 and 100 K under the biaxial compressive strains of -0.02 and -0.04 , respectively. These T_c values are much higher than the liquid nitrogen temperature (77 K), which facilitates the experimental achievement of promising magnetic properties in the $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets.

Finally, the stable $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets also offer new building blocks for the van der Waals heterostructures (VDWHs) [66]. Since the lattice constants of $\text{MoN}_2\text{Al}_2\text{O}_2$ and $\text{MoN}_2\text{B}_2\text{S}_2$ nanosheets are close to the MoSi_2N_4 one, the lattice mismatches between them are less than 3%. Thus a commensurable bilayer structure can be constructed from their 1×1 unit cells. Following the convention of MoSi_2N_4 bilayers [67, 68], five stacking geometries, including AA, AB, AB^* , AC, AC^* , are considered for the $\text{MoN}_2\text{X}_2\text{Y}_2$ - MoSi_2N_4 VDWHs. The AB and AC stacking structures are found to be the most stable for the $\text{MoN}_2\text{Al}_2\text{O}_2$ - MoSi_2N_4 and $\text{MoN}_2\text{B}_2\text{S}_2$ - MoSi_2N_4 ones, respectively. The corresponding binding

energies E_b , which are the energy differences between the heterostructure and isolated layers, are calculated as -0.222 and -0.212 eV/f.u. for them. These values correspond to an interlayer interaction of $30\text{--}28$ meV/ \AA^2 in the $\text{MoN}_2\text{X}_2\text{Y}_2$ - MoSi_2N_4 VDWHs, which is comparable to the common van der Waals interactions in layered compounds (~ 20 meV/ \AA^2) [69]. The band structures of $\text{MoN}_2\text{X}_2\text{Y}_2$ - MoSi_2N_4 VDWHs are depicted in the Figs. 4(a) and (d). It can be seen that the bands of $\text{MoN}_2\text{X}_2\text{Y}_2$ and MoSi_2N_4 layers are clearly recognized. There is no interlayer hybridization between them around the Fermi level. For the $\text{MoN}_2\text{B}_2\text{S}_2$ - MoSi_2N_4 VDWH, the top valence band is originated from the $\text{MoN}_2\text{B}_2\text{S}_2$ layer while the bottom conduction band is from the MoSi_2N_4 one. Thus, a staggered-gap type-II band alignment is formed in this $\text{MoN}_2\text{B}_2\text{S}_2$ - MoSi_2N_4 VDWH. Similar band feature is also obtained in the $\text{MoN}_2\text{Al}_2\text{O}_2$ - MoSi_2N_4 system, i.e. the top valence and bottom conduction bands are also originated from different layers. However, the top valence band at the Γ point is higher than the bottom conduction band at K point, which leads to a metallic behaviour. This stems from the big band offset between the isolated $\text{MoN}_2\text{Al}_2\text{O}_2$ and MoSi_2N_4 nanosheets, where the CBM of MoSi_2N_4 layer is even 0.189 eV lower than the VBM of $\text{MoN}_2\text{Al}_2\text{O}_2$ layer. Thus according to the Schottky-Mott rule [70–72], there will be a broken-gap type-III band alignment existing in the $\text{MoN}_2\text{Al}_2\text{O}_2$ - MoSi_2N_4 VDWH. Interestingly, the band alignment of these $\text{MoN}_2\text{X}_2\text{Y}_2$ - MoSi_2N_4 VDWHs can be further modulated by the strain. As shown in Figs. 4(b) and (e), the absolute energy of CBM

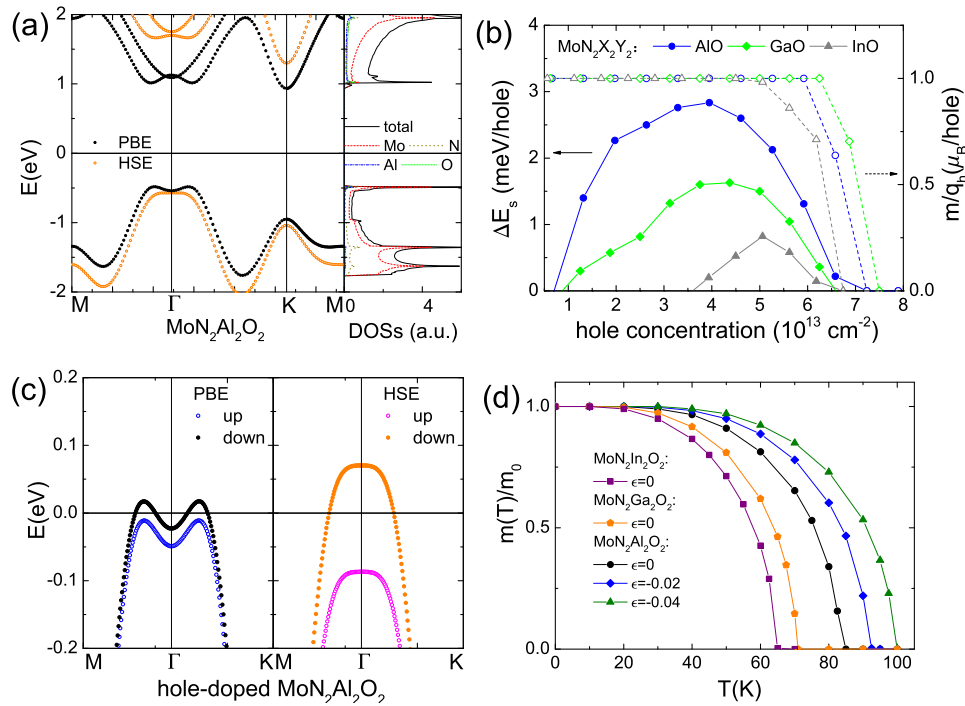


Fig. 3. (a) The PBE and HSE band structures of MoN₂Al₂O₂ nanosheet. (b) The spin-polarization energy and magnetic moment of hole-doped MoN₂X₂Y₂ (XY = AlO, GaO, InO) nanosheets. (c) The spin-polarized PBE and HSE band structures of hole-doped MoN₂Al₂O₂ nanosheet with the q_h = 4 × 10¹³ cm⁻². (d) The variation of the magnetic moment versus temperature in the MoN₂X₂Y₂ nanosheets.

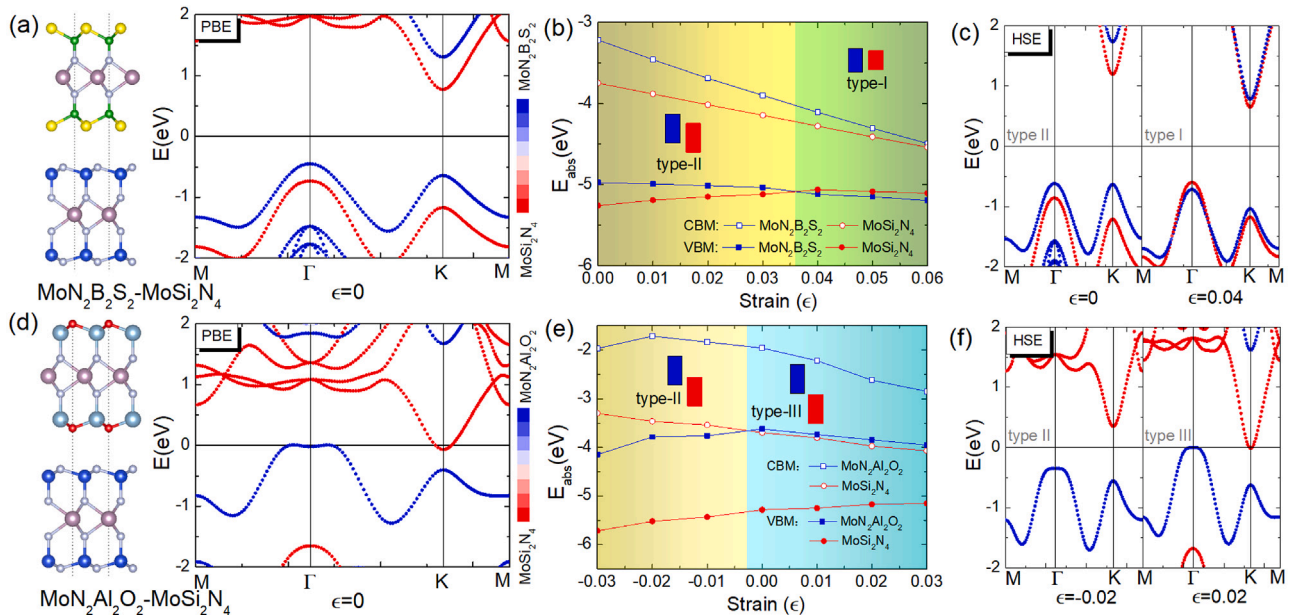


Fig. 4. [(a), (d)] The atomic structures and PBE band structures of MoN₂B₂S₂-MoSi₂N₄ and MoN₂Al₂O₂-MoSi₂N₄ heterostructures. [(b), (e)] The variations of absolute energies of band edges in different building layers versus strains. Here, the vacuum level is adopted as the zero points. [(c), (f)] The corresponding HSE band structures of strained MoN₂B₂S₂-MoSi₂N₄ and MoN₂Al₂O₂-MoSi₂N₄ heterostructures.

is lowered (raised) by the tensile (compressive) strain, while the VBM presents a converse variation trend. Thus for the MoN₂Al₂O₂-MoSi₂N₄ VDWH, a compressive strain of $\epsilon \leq -0.01$ will shift the CBM above the VBM and transform the system into a type-II band alignment. While in the MoN₂B₂S₂-MoSi₂N₄ system, the variations of band edge in the MoSi₂N₄ layer are more pronounced than the MoN₂B₂S₂ one.

Consequently, a transition from the type-II to type-I band alignment is present in the MoN₂B₂S₂-MoSi₂N₄ VDWH under the tensile strain of $\epsilon \geq 0.04$. To verify these band alignment transformations, the HSE calculations are performed on the MoN₂X₂Y₂-MoSi₂N₄ VDWHs. As in Figs. 4 (c) and (f), the HSE results are consistent with the PBE ones that all the band alignment types, including type I, II, and III, can emerge in

the strained $\text{MoN}_2\text{X}_2\text{Y}_2$ - MoSi_2N_4 systems. Therefore, these $\text{MoN}_2\text{X}_2\text{Y}_2$ - MoSi_2N_4 VDWHs will be promising platforms to achieve multiple band alignments for nanoscale electronic devices.

4. Conclusion

In summary, we have performed a comprehensive first-principles study on the group III–VI $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets, which are the isostructural and isoelectronic analogues of MoSi_2N_4 system. It is found that (1) among the sixteen candidates, there are nine III–VI XY combinations that can form stable $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets, which possess robust dynamical, energetic, and thermal stability. (2) These $\text{MoN}_2\text{X}_2\text{Y}_2$ nanosheets can be indirect-gap semiconductors or metals depending on the XY compositions. For the semiconducting systems, a linear relationship is present between the band gap and lattice constant. Regarding to the metallic ones with $\text{XY}=\text{AlS}$, GaS , a metal–semiconductor transition can be easily triggered by small strains. (3) In particular, the Mexican-hat-like valence bands emerge in three $\text{MoN}_2\text{X}_2\text{Y}_2$ ($\text{XY}=\text{AlO}$, GaO , InO) nanosheets, which can be converted into ferromagnetic half-metals via the hole doping. (4) When the $\text{MoN}_2\text{X}_2\text{Y}_2$ ($\text{XY}=\text{BS}$, AlO) nanosheets are coupled with the MoSi_2N_4 system, the formed van der Waals heterostructures exhibit versatile and strain-tunable band alignments, including the straddling-gap type-I, staggered-gap type-II, and broken-gap type-III ones. Our study demonstrates the variation of surface layer provides a new degree to tailor the electronic structures of MA_2Z_4 -based materials, which enable them intriguing nano-electrics, spintronics and device applications.

CRedit authorship contribution statement

Yi Ding: Conceptualization, Methodology, Writing – original draft.
Yanli Wang: Software, Writing – review & editing.

Declaration of competing interest

The authors declare that they have no known competing financial interests or personal relationships that could have appeared to influence the work reported in this paper.

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Appendix A. Supplementary data

Supplementary material related to this article can be found online at <https://doi.org/10.1016/j.apsusc.2022.153317>.

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